L Number	Hits	Search Text	DB	Time stamp
1	226277	plasma	USPAT; US-PGPUB	2004/09/24 16:14
2	3587	(oxygen or "O.sub.2") adj radicals	USPAT; US-PGPUB	2004/09/24 16:15
3	28618	gate adj insulat$3	USPAT; US-PGPUB	2004/09/24 16:15
4	10063	gate adj dielectric	USPAT; US-PGPUB	2004/09/24 16:16
5	34311	gate adj oxide	USPAT; US-PGPUB	2004/09/24 16:16
6	342480	hydro$1carbon$1	USPAT; US-PGPUB	2004/09/24 16:17
7	2	((gate adj insulat$3) or (gate adj dielectric) or (gate adj oxide)) same plasma same ((oxygen or "O.sub.2") adj radicals) same hydro$1carbon$1	USPAT; US-PGPUB	2004/09/24 16:25
8	595149	hydrogen or "H.sub.2"	USPAT; US-PGPUB	2004/09/24 16:26
9	124997	carbon adj dioxide	USPAT; US-PGPUB	2004/09/24 16:26
10	139612	"CO.sub.2"	USPAT; US-PGPUB	2004/09/24 16:27
11	4	plasma same ((oxygen or "O.sub.2") adj radicals) same hydro$1carbon$1 same (hydrogen or "H.sub.2") same ((carbon adj dioxide) or "CO.sub.2")	USPAT; US-PGPUB	2004/09/24 16:33
12	16288	(clean$3 or remov$3) near3 hydro$1carbon$1	USPAT; US-PGPUB	2004/09/24 16:46
13	16	((gate adj insulat$3) or (gate adj dielectric) or (gate adj oxide)) and ((plasma or ((oxygen or "O.sub.2") adj radicals)) same ((clean$3 or remov$3) near3 hydro$1carbon$1))	USPAT; US-PGPUB	2004/09/24 16:37
14	9831	plasma adj (reactor or system or chamber or apparatus)	USPAT; US-PGPUB	2004/09/24 16:41
15	0	(plasma adj (reactor or system or chamber or apparatus)) and (((gate adj insulat$3) or (gate adj dielectric) or (gate adj oxide)) same ((clean$3 or remov$3) near3 hydro$1carbon$1))	USPAT; US-PGPUB	2004/09/24 16:43
16	5	(((gate adj insulat$3) or (gate adj dielectric) or (gate adj oxide)) same ((clean$3 or remov$3) near3 hydro$1carbon$1))	USPAT; US-PGPUB	2004/09/24 16:45
17	128607	contaminant$1	USPAT; US-PGPUB	2004/09/24 16:46
18	37968	(clean$3 or remov$3) near3 contaminant$1	USPAT; US-PGPUB	2004/09/24 16:46
19	155	((gate adj insulat$3) or (gate adj dielectric) or (gate adj oxide)) same ((clean$3 or remov$3) near3 contaminant$1)	USPAT; US-PGPUB	2004/09/24 16:47
20	27	(((gate adj insulat$3) or (gate adj dielectric) or (gate adj oxide)) same ((clean$3 or remov$3) near3 contaminant$1)) same plasma	USPAT; US-PGPUB	2004/09/24 16:53
21	538238	"N.sub.2" or nitrogen	USPAT; US-PGPUB	2004/09/24 16:54
22	5597	plasma near3 ("N.sub.2" or nitrogen)	USPAT; US-PGPUB	2004/09/24 16:54
23	476654	"O.sub.2" or oxygen	USPAT; US-PGPUB	2004/09/24 16:55
24	18471	plasma near3 ("O.sub.2" or oxygen)	USPAT; US-PGPUB	2004/09/24 16:55

25	21	((clean$3 or remov$3) same (plasma near3 ("N.sub.2" or nitrogen))) and (((in adj situ) or in$1situ) same (plasma near3 ("O.sub.2" or oxygen)))	USPAT; US-PGPUB	2004/09/24 17:39
26	39	((clean$3 or remov$3) same (plasma near3 ("O.sub.2" or oxygen))) and (((in adj situ) or in$1situ) same (plasma near3 ("N.sub.2" or nitrogen)))	USPAT; US-PGPUB	2004/09/24 17:11
27	101	(in$1situ or (in adj situ)) adj plasma adj clean$3	USPAT; US-PGPUB	2004/09/24 17:12
28	15	((gate adj insulat$3) or (gate adj dielectric) or (gate adj oxide)) and ((in$1situ or (in adj situ)) adj plasma adj clean$3)	USPAT; US-PGPUB	2004/09/24 17:17
29	1993	airborne adj2 contaminant$1	USPAT; US-PGPUB	2004/09/24 17:18
30	30	((gate adj insulat$3) or (gate adj dielectric) or (gate adj oxide)) and (plasma same ("O.sub.2" or oxygen) same (hydro$1carbon$1 or (airborne adj2 contaminant$1)) same (remov$3 or clean$3)) and (plasma same ("N.sub.2" or nitrogen))	USPAT; US-PGPUB	2004/09/24 17:21
31	52	(clean$3 or remov$3) same ((gate adj insulat$3) or (gate adj dielectric) or (gate adj oxide)) same (hydro$1carbon$1 or contaminant$1) same plasma	USPAT; US-PGPUB	2004/09/24 18:15
35	137421	silicon adj $2oxide	USPAT; US-PGPUB	2004/09/24 19:02
36	134924	"SiO.sub.2"	USPAT; US-PGPUB	2004/09/24 19:02
37	6969	SiO2	USPAT; US-PGPUB	2004/09/24 19:03
38	10279	plasma adj treatment	USPAT; US-PGPUB	2004/09/24 19:04
39	79759	(remov$3 or clean$3 or etch$3) with (hydro$1carbon$1 or contaminant$1)	USPAT; US-PGPUB	2004/09/24 19:05
40	6	((silicon adj $2oxide) or "SiO.sub.2" or SiO2) same (plasma adj treatment) same ((remov$3 or clean$3 or etch$3) with (hydro$1carbon$1 or contaminant$1))	USPAT; US-PGPUB	2004/09/24 19:07
41	286	((silicon adj $2oxide) or "SiO.sub.2" or SiO2) same plasma same ((remov$3 or clean$3 or etch$3) with (hydro$1carbon$1 or contaminant$1))	USPAT; US-PGPUB	2004/09/24 19:52
42	514055	silicon or Si	USPAT; US-PGPUB	2004/09/24 19:53
43	72472	polysi$5	USPAT; US-PGPUB	2004/09/24 19:54
44	4871	((silicon or Si) or polysi$5) same (clean$3 or remov$3) same (hydro$1carbon$1 or contaminant$1)	USPAT; US-PGPUB	2004/09/24 19:57
45	555	((silicon or Si) or polysi$5) same (clean$3 or remov$3) same (hydro$1carbon$1 or contaminant$1) same plasma	USPAT; US-PGPUB	2004/09/24 21:18
46	17975	((silicon or Si) or polysi$5) same (clean$3 or remov$3) same plasma	USPAT; US-PGPUB	2004/09/24 21:19
47	3217	((silicon or Si) or polysi$5) same ((clean$3 or remov$3) same (plasma near2 ("O.sub.2" or oxygen)))	USPAT; US-PGPUB	2004/09/24 21:20
48	64	((silicon or Si) or polysi$5) same (((clean$3 or remov$3) with (hydro$1carbon$1 or contaminant$1)) same (plasma near2 ("O.sub.2" or oxygen)))	USPAT; US-PGPUB	2004/09/24 21:24
49	339	(plasma adj clean$3) near2 ("O.sub.2" or oxygen)	USPAT; US-PGPUB	2004/09/24 21:30

50	98	((silicon or Si) or polysi$5) same ((plasma adj clean$3) near2 ("O.sub.2" or oxygen))	USPAT; US-PGPUB	2004/09/24 22:10
51	80669	(remov$3 or purg$3) near2 $3product$1	USPAT; US-PGPUB	2004/09/24 22:11
52	126	(((silicon or Si) or polysi$5) same ((clean$3 or remov$3) same (plasma near2 ("O.sub.2" or oxygen)))) and ((remov$3 or purg$3) near2 $3product$1)	USPAT; US-PGPUB	2004/09/24 22:11